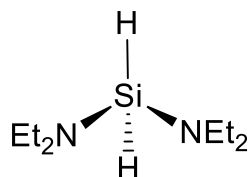


Catalog # 98-8810 Bis(diethylamino)silane, 99% (99.999%-Si) BDEAS PURATREM



Technical Notes:

1. Plasma-Assisted ALD for the Conformal Deposition of SiO₂
2. Room-Temperature ALD of Metal Oxide Thin Films by Energy-Enhanced ALD
3. Atomic Layer Deposition of Silica on Carbon Nanotubes
4. Area-Selective Atomic Layer Deposition of SiO₂ Using Acetylacetone as a Chemoselective Inhibitor in an ABC-Type Cycle

References:

1. *J. Electrochem. Soc.*, **2012**, 159, H277.
2. *Chem. Vap. Deposition*, **2013**, 19, 125.
3. *Chem. Mater.*, **2017**, 29, 4920.
4. *ACS Nano*, **2017**, 11, 9303.